



Sheet 1 of 1

Form PTO-1449
(Rev. 8-83)U.S. Department of Commerce
Patent and Trademark Office

Atty. Docket No. 0756-945

Serial No. 08/169,127

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant Hisato SHINOHARA et al.

Filing Date December 20, 1993

Group 1586

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
<i>MSH</i>	4 1 8 1 5 6 3	1980 <i>Jun</i>	Miyaka et al.	427	53.1	
<i>MSH</i>	4 2 9 2 0 9 2	1981 <i>Sept</i>	Hanak	427	53.1	
<i>MSH</i>	4 4 1 3 0 2 0	1983 <i>Nov</i>	McKee et al.	427	53.1	
<i>MSH</i>	4 6 8 0 8 5 5	1987 <i>July</i>	Yamazaki et al.	156	1643 20	
<i>MSH</i>	4 7 1 3 5 1 8	1987 <i>June</i>	Yamazaki et al.	427	53.1	
<i>MSH</i>	4 7 5 3 8 5 5	1988 <i>June</i>	Haluska et al.	427	58	12/4/86
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<i>MSH</i>	4 7 8 6 3 5 8	1988 <i>Nov.</i>	Yamazaki et al.	156	643	8/7/87

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Document Number	Date	Country	Class	Subclass	Translation Yes No
5 7 7 9 1 4	1982	no such number in previous case			
5 7 1 5 8 6 2 3	1982	Japan			✓
63 1 9 5 1 4 8	1988	Japan			✓

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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2/14/94

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09/04/2002

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